

Application
Number

IDS Flag Clearance for Application 10804053

IDS
Information

Content	Mailroom Date	Entry Number	IDS Review	Reviewer
M844	03-19-2004	10	<input checked="" type="checkbox"/>	01-03-2006 13:20:36 LPham
M844	04-04-2006	31	<input checked="" type="checkbox"/>	06-25-2006 12:34:50 LPham

	Type	Hits	Search Text
1	BRS	16521	(film or layer or films or layers) near3 target
2	BRS	2191	S4 same chamber
3	BRS	1423	S4 near10 (gas or gases)
4	BRS	591	S6 same (substrate)
5	BRS	39366	(silicon adj2 nitride) adj2 (film or layer)
6	BRS	3667	S8 near15 (gas or gases)
7	BRS	14	S7 same S9
8	BRS	3	S10 same chamber
9	BRS	40	S4 same S9
10	BRS	10	S12 same chamber
11	BRS	6	substrat same chamber
12	BRS	63325	substrate same chamber
13	BRS	1262	S4 same S15
14	BRS	3	S9 same S16
15	BRS	40920	(silicon adj2 nitride) adj2 (film or layer or films or layers)
16	BRS	143	S18 near3 target
17	BRS	70	S19 same substrate
18	BRS	29	S20 same chamber
19	BRS	19143	(silicon adj2 nitride) adj2 (film or layer or films or layers)
20	BRS	18	S22 near3 target
21	BRS	2	S19 near20 (after or before) near20 substrate
22	BRS	492	silicon adj2 nitrided
23	BRS	492	silicon adj2 nitrided
24	BRS	97861	silicon adj2 nitride
25	BRS	9	nitrogen near10 S27 near10 (disilane or trisilane)
26	BRS	2165	S27 near5 (plasma adj2 cvd)
27	BRS	27969	cvd near10 (sputtering or sputter or sputtered)
28	BRS	60	S30 near10 (("same" or "single" or "a" or "one") adj2 chamber)

	DBs
1	US-PGPUB; USPAT
2	US-PGPUB; USPAT
3	US-PGPUB; USPAT
4	US-PGPUB; USPAT
5	US-PGPUB; USPAT
6	US-PGPUB; USPAT
7	US-PGPUB; USPAT
8	US-PGPUB; USPAT
9	US-PGPUB; USPAT
10	US-PGPUB; USPAT
11	US-PGPUB; USPAT
12	US-PGPUB; USPAT
13	US-PGPUB; USPAT
14	US-PGPUB; USPAT
15	US-PGPUB; USPAT
16	US-PGPUB; USPAT
17	US-PGPUB; USPAT
18	US-PGPUB; USPAT
19	USOCR; EPO; JPO; DERWENT; IBM_TDB
20	USOCR; EPO; JPO; DERWENT; IBM_TDB
21	US-PGPUB; USPAT
22	US-PGPUB; USPAT
23	US-PGPUB; USPAT
24	US-PGPUB; USPAT
25	US-PGPUB; USPAT
26	US-PGPUB; USPAT
27	US-PGPUB; USPAT
28	US-PGPUB; USPAT